

FORM PTO-1449  
(REV. 7-80)U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICEAPP. DOCKET NO.  
RD-28,667SERIAL NO.  
09/683,149INFORMATION DISCLOSURE STATEMENT BY APPLICANT  
LIST OF ITEMSApplicant  
Marc (NMN) Schaepkens # 2Filing Date  
11/27/2001

Group

## U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
pt	A1	4,871,580	10/3/89	Schram et al.		
pt	A2	4,957,062	9/18/90	Schuurmans et al.		
pt	A3	5,120,568	6/9/92	Schuurmans et al.		
pt	A4	6,213,049	4/10/01	Yang		
	A5					

## FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
	B1					
	B2					

## OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, etc.)

pt	C1	"Temperature and Growth-Rate Effects on the Hydrogen Incorporation in Hydrogenated Amorphous Silicon", WMM Kessels et al., Department of Applied Physics, Eindhoven University of Technology, 1998, pp 29-33.				
pt	C2	"Improvement of Hydrogenated Amorphous Silicon Properties With Increasing Contribution of SiH <sub>4</sub> to Film Growth", WMM Kessels et al., Department of Applied Physics, Eindhoven University of Technology, pp 107-110.				
pt	C3	Application Serial No. 09/681,820, filed June 11, 2001, "Apparatus and Method for Large Area Chemical Vapor Deposition Using Multiple Expanding thermal Plasma Generators".				
pt	C4	Specification RD-28,484 - "Apparatus and Method for Depositing Large Area Coatings on Non-Planar Surfaces", Marc (NMN) Schaepkens 09/683,148				
	C5					
	C6					
	C7					
	C8					

EXAMINER

P. Hassanza del

DATE CONSIDERED

6-7-02

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant